Detail Design for

Smart & Small Structures (Triple S)

MINA: CSKim and JBPark

Design for Manufacturing

Contents

- FIB parameters
- Material selection
- Detail design
 - Ion beam parameter
 - Processing parameter
 - Geometric parameter
- Evaluation
 - Efficiency
 - Geometric error based on ion beam defect
 - Final shape evaluation
- Pre-test for ion beam selection
- On-going work
- Priority work
- Conclusion

Project plan

- □ Mission statement & Brain storming
- Conceptual design
- □ Pre-study
 - Python
 - Design of Experiment
- Detail design
 Beam current, Dimension, and so on
- Fabrication
- Analysis
 - Relative parameter extraction
- Evaluation
- Documentation

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Focused Ion Beam Nano/Microfabrication

	Difficulties	Angle-Dependent sputtering	Non-constant Sputter rate	Scattered Ions		
P	Ectimation	Side Wall Effect	Aspect ratio	Bottom Shape of Etched Structures		
A R	Estimation	Sputter Yield	Redeposition	Deposition Yield		
A M						
E		Ion Species	Ion Dose	Ion Energy		
I E R	Descenter	Incidence Angle	Substrate	Dwell Time		
S	Parameters	Beam Overlapping	Precursor Gas	Scan Step Size		
		Structural Change by Ion Implantation	Beam Current	Refresh Time		

Material Selection

□ Silicon substrate

- Easy to get
- Good surface roughness for evaluation



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Detail Design



Ion Beam Parameter

- Ion beam parameter
 - Spot diameter [nm]
 - Ion beam current [A]
 - Current density [A/cm²]



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Ion Beam Parameter

Ion beam current [pA]										
10.2		High curre	ent ion bea	ıms‼						
89.2			: Effective for large milling area							
282			Short tabricatio	on time (expensi	ve costj					
708	-				Current Density					
		No	Snot Siza (nm)	Ion Current (nA)	Current Density					
3027	_	No.	Spot Size (nm)	Ion Current (pA)	(A/cm ²)					
3027 6640	-	No. 1	Spot Size (nm)	lon Current (pA) 6640.625	(A/cm ²)					
3027 6640 13427	-	No. 1 2	Spot Size (nm) 115 160	lon Current (pA) 6640.625 13427.734	63.96 66.81					

Processing Parameter



Geometric Parameter





No. of slice (N)

Evaluation



where w_a is the width, l_a is the length, and z_a is the thickness of a deposited carbon structure.

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Evaluation



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Evaluation

Geometry errors by ion beam defect



Horizontal Length [nm]

Definition of sputtered feature for evaluating nano/microscale effect

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<image>

Pre-Test 1



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Pre-Test 2



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Pre-Test 3

		Data name : over81.ols Commont :			
Beam overlapping	110	1	15 3		
 K100 K100<td></td><td>600 32 500 41 000 84 60</td><td>ti and ti and ti</td><td>45.000 0000 = 1.09x = 1.4x 1.4x - 2.22 0.1 CP-H</td><td></td>		600 32 500 41 000 84 60	ti and ti	45.000 0000 = 1.09x = 1.4x 1.4x - 2.22 0.1 CP-H	
8.000 8.000 15.000 12.000 48.000 54.000	Parameter		Conditio	ı	
£ 100	Field of View (µm)		150		
	Pixel Size (mm)		187.5		
1559. and the second way	Defined Area (μm²)		25 (5 x 5))	
2.40- Mm M	Ion Energy (KeV)		30		
1220.	Ion Dose (10 ¹⁵ ions/cm ²)		3000		
0.000 16.000 32.000 48.000 54.000	Spot Size (nm)	115	160	2	200
4500	Probe Current (nA)	6.6	13.4	2	23.2
2440	Current Density (A/cm ²)	63.96	66.81	7	4.17
1228- W	Dwell Time (µs)		1	•	
8.000 8.000 16.007 32.014 48.020 64.027	Beam Overlap (%)	-90 -50	0	50	90
	Refresh Time (ms)		0		

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On-going work: Python





On-going work: Python



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On-going work: Design of Experiment

□ 4 factor 3 level

each case of experiment will be performed twice at least

	lon dose (A)	Dwell time (B)	Beam overlap (C)	No. of slice (D)
1		0.5	-50	10
2	Undetermined	5	0	20
3		10	50	30

L₉(3⁴) Orthogonal array

No		Fo	actor				Result					
	А	В	С	D	Sputter Yield	Feature definition	Side wall angle	Radius of curvature				
1	1	1	1	1								
2	1	2	2	2								
3	1	3	3	3								
4	2	3	2	3								
5	2	1	3	1								
6	2	2	1	2								
7	3	1	3	2								
8	3	2	1	3								
9	3	3	2	1								

Priority Work

□ Finding ion dose

Find the ion dose (D_0) satisfying the aspect ratio 1

- Circular
 D_C=2/3 D₀
- Rectangle
 D_R1/2 D₀



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Conclusion

Determined ion beam condition

Parameter	Condition
Field of View (1011)	120
Pixel Size (nm)	150
Defined Area (µm ²)	5 x 5
Ion Energy (KeV)	30
lon Dose (ions/cm²)	Not determined
Spot Size (nm)	150
Probe Current (pA)	6640
Current Density (A/ cm^2)	37.59
Dwell Time (µs)	Variation 0.5, 5, 10
Beam Overlap (%)	Variation -50, 0, 50
Refresh Time (ms)	0
Slice Number	Variation 10, 20, 30

Schedule boards

Plan _					W	'eek (20) March	2006 -	~ Mid J	une 200	06)									
		1	2	3	4	5	6	7	8	9	10	11	12	13						
Mission statement and Brain storming																				
Conceptual Design																				
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Thanks Any Questions??